

Thermal Modeling of 3D Polylithic Integration

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Interconnect bandwidth
Figure 1: Motivation

- 3D integration of functional chiplets is primarily realized via TSV-based 3D stacking or monolithic 3D integration.
- However, there is a performance gap between TSVbased 3D and 3D monolithic ICs in terms of bandwidth and interconnect density.

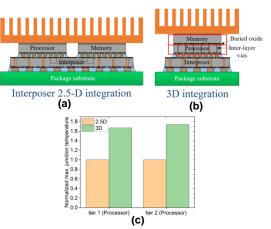


Figure 2: (a) Interposer-based 2.5-D and (b) 3D integration examples. (c) Maximum junction temperatures: Tier powers: 1. processor (150W), 2. processor (150W).

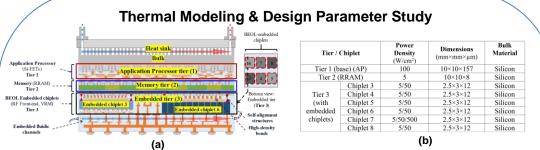


Figure 3: (a) 3D Seamless off-chip Connectivity (SoC+) concept: BEOL-embedded chiplet integration. (b) thermal simulations: design specifications & assumptions

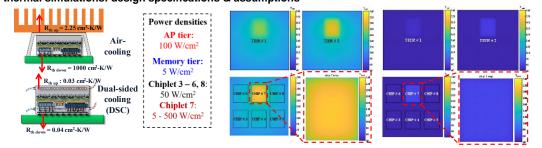


Figure 4: Considered cooling techniques and tier power densities for thermal evaluation and steady state evaluation

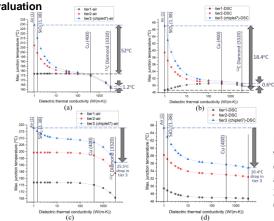


Figure 5: Maximum junction temperatures as a function of varying dielectric thermal conductivity in 1) all tiers with (a) air and (b) DSC and 2) just embedded tier with (c) air and (d) DSC.

Transient Thermal Analysis

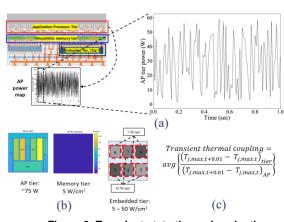


Figure 6: Transient state thermal evaluation

Conclusion

We have presented a thermal study for 3D polylithic integration as a function of tier power density, dielectric thermal conductivity, and transient power variation to identify thermal limits and challenges in such integration approaches.

